

Double Inspection of Reticle or Wafer

ABSTRACT OF THE DISCLOSURE

During mask or reticle inspection, each region is scanned
5 at least twice, using an overlap between each pair of consecutive frames. System contamination and camera blemishes have approximately constant frame coordinates, while mask defects have constant reticle coordinates, but inconstant scan frame coordinates. True defects are detected at different coordinates in
10 consecutive frames with a known displacement therebetween.